

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi TAKEI et al.

Application No.: 10/553,675

Filed: October 31, 2005

Docket No.: 125640

For: POROUS UNDERLAYER COATING AND UNDERLAYER COATING FORMING COMPOSITION FOR FORMING POROUS UNDERLAYER COATING

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

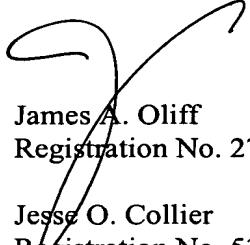
Sir:

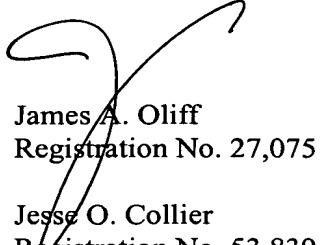
Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- 2. Relevance of references 1-6 and 12-15 is discussed in the present specification.
- 3. The references 7-11 were cited in the International Search Report. An English language version of the International Search Report is attached for the Examiner's information.
- 4. In accordance with 37 CFR §1.98(a)(2)(ii), copies of any U.S. patents and patent application publications are not attached.
- 5. English language Abstracts of the non-English language references 3-10 and 12 are attached hereto.

6. A computer-generated English language translation of the following Japanese Patent Publication has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See References 3-11.

Respectfully submitted,


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DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461
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Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 125640	APPLICATION NO. 10/553,675	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANTS Satoshi TAKEI et al.		
				FILING DATE October 31, 2005		
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	1	5,919,599	07/06/1999	Meador et al.		
	2	5,693,691	12/02/1997	Flaim et al.		
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
	3	JP A 2000-294504 w/abstr. + trans.	10/20/2000	Japan		
	4	JP A 2002-47430 w/abstr. + trans.	02/12/2002	Japan		
	5	JP A 2002-190519 w/abstr. + trans.	07/05/2002	Japan		
	6	JP A 2002-128847 w/abstr. + trans.	05/09/2002	Japan		
	7	JP A 2002-207295 w/abstr. + trans.	07/26/2002	Japan		
	8	JP A 2002-207296 w/abstr. + trans.	07/26/2002	Japan		
	9	JP A 2003-57828 w/abstr. + trans.	02/28/2003	Japan		
	10	JP A 2001-272506 w/abstr. + trans.	10/05/2001	Japan		
	11	JP A 2000-512402 w/translation	09/19/2000	Japan		
	12	WO 02/05035 A1 w/abstract	01/17/2002	WIPO		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)						
	13	Lynch et al., "Properties and Performance of Near UV Reflectivity Control Layers," SPIE Vol. 2195, pp. 225-229, 1994				
	14	Taylor et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography," SPIE Vol. 3678, pp. 174-185, March 1999				
	15	Meador et al., "Recent Progress in 193 nm Antireflective Coatings," SPIE Vol. 3678, pp. 800-809, March 1999				
EXAMINER					DATE CONSIDERED	
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						

Date: December 19, 2005